



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **Koji NOZAKI et al.**

Group Art Unit: **1752**

Application Number: **10/623,679**

Examiner: **Amanda C. Walke**

Filed: **July 22, 2003**

Confirmation Number: **5083**

For: **RESIST PATTERN THICKENING MATERIAL, RESIST
PATTERN AND PROCESS FOR FORMING THE SAME, AND
SEMICONDUCTOR DEVICE AND PROCESS FOR
MANUFACTURING THE SAME**

Attorney Docket Number: **030891**

Customer Number: **38834**

RESPONSE

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

February 22, 2008

Sir:

This paper is filed in response to the Office Action dated October 2, 2007, the response due date extended to March 2, 2008 by a two-months Extension of Time.

Remarks begin on page 2 of this paper.